

FIG. 1

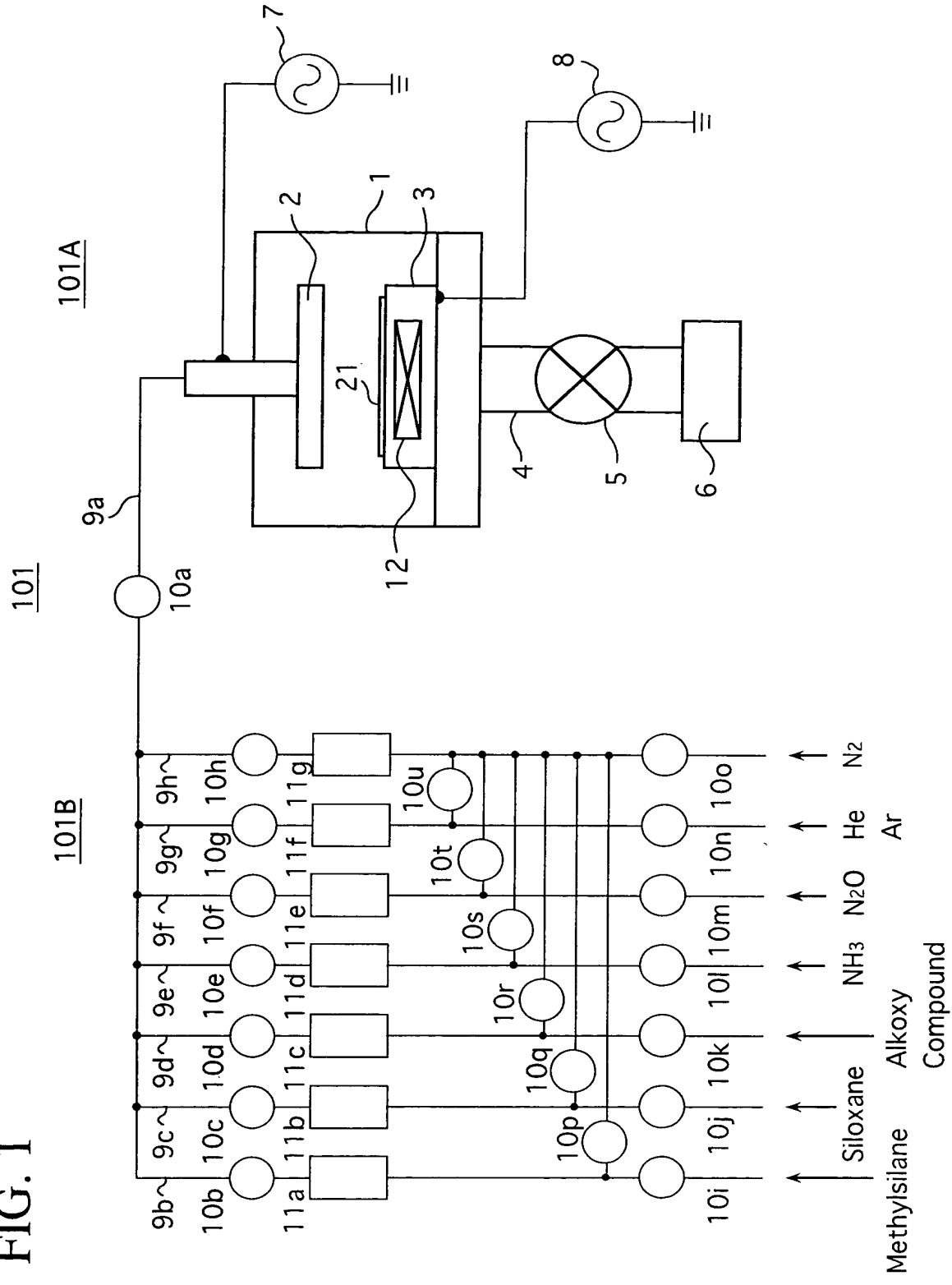


FIG. 2

Formed Film Indication	1(2)	3(4)	5(6)	7(8)	9(10)	11(12)	13(14)	15(16)	17
Methylsilane	○	○	○	○	○	○			○
Siloxane							○		
Alkoxy Compound								○	
N ₂	○		○	○		○	○	○	
NH ₃		○	○		○	○	○	○	
N ₂ O				○	○	○	○	○	○
O ₂				(○)	(○)	(○)	(○)	(○)	(○)
Ar, He	(○)	(○)	(○)	(○)	(○)	(○)	(○)	(○)	
Plasma Process	(○)	(○)	(○)	(○)	(○)	(○)	(○)	(○)	(○)
Film Constitution	SiN	SiN	SiN	SiON	SiON	SiON	SiON	SiON	SiO

Note 1) Non-parenthesized numeral in the formed film indication column corresponds to the case where Ar or He is not added, and parenthesized numeral corresponds to the case where Ar or He is added.

Note 2) (○) in the Ar, He column indicates that both cases where Ar or He is added and is not added are contained.

Note 3) (○) in the O₂ column indicates that both cases where O₂ is added and is not added are contained.

Note 4) (○) in the plasma process column indicates that both cases where the plasma process is applied to the formed film and is not applied to the same are contained.

FIG. 3

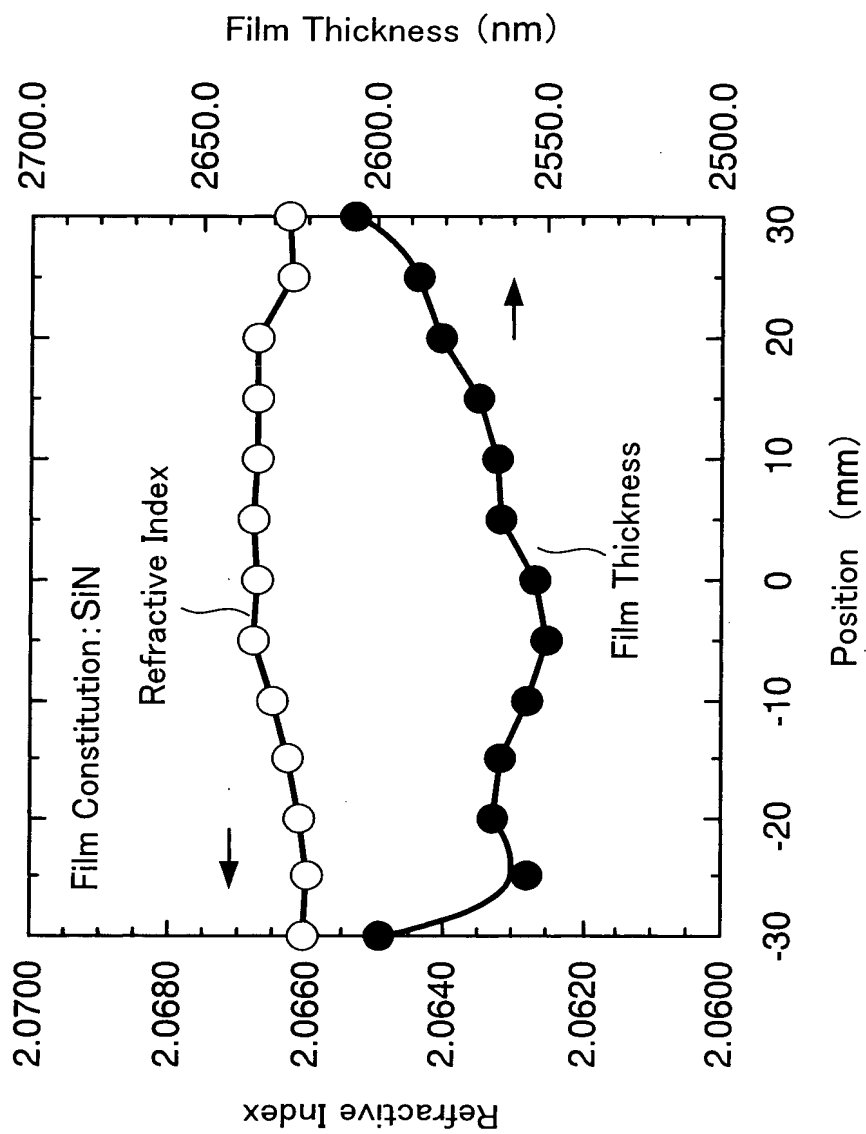


FIG. 4

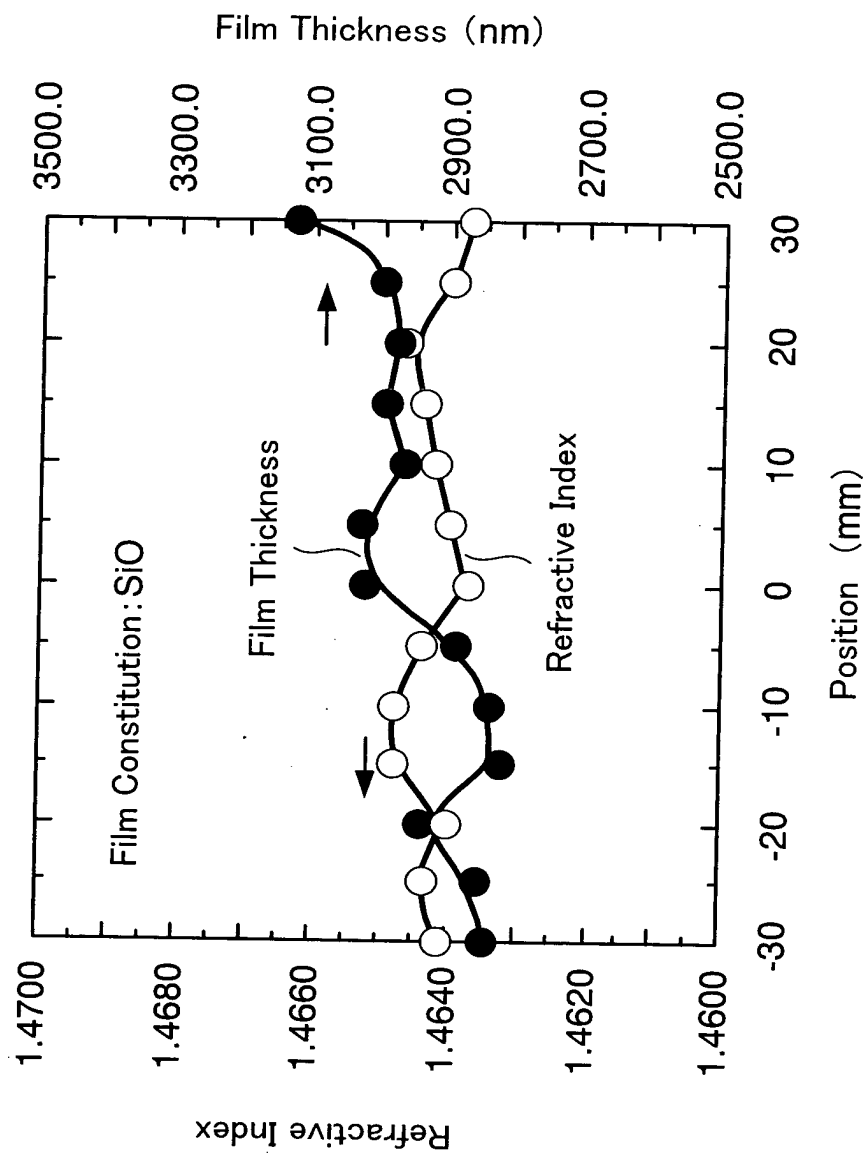


FIG. 5A

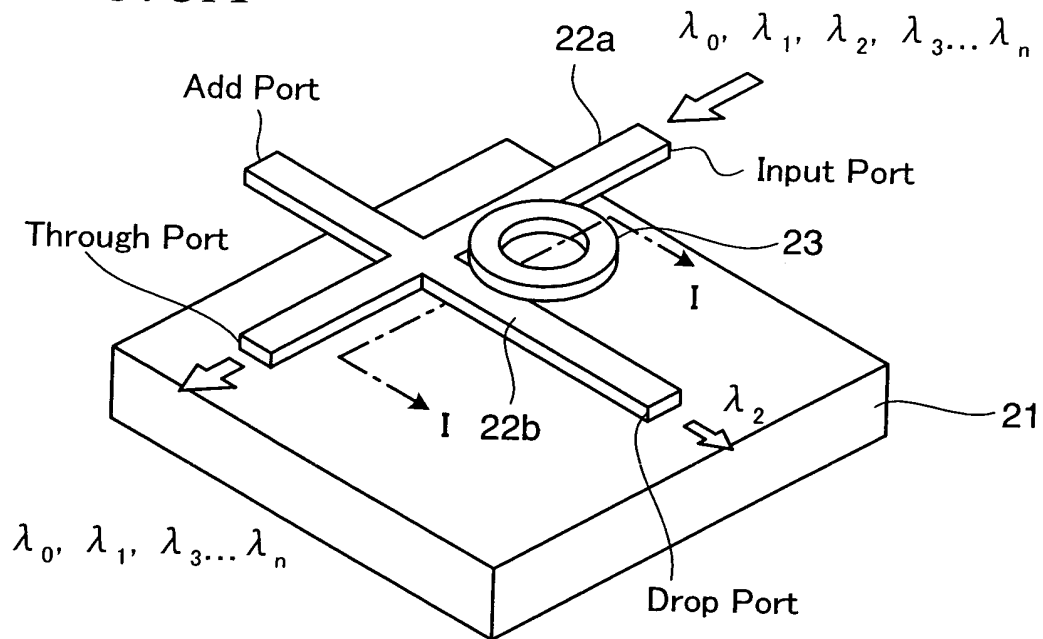


FIG. 5B

